CHANAL FAX CEMEN

JUN 1 5 2004



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Kay Ming Lee, Cheng-Wen Fan, Jiunn-Ren

5 Hwang, Chih-Chiang Liu

Examiner: MOHAMEDULLA, SALEHA R

Filing Date: 05/12/2002 Art Unit: 1756

App. No.: 10/063,779 Docket No.: NAUP0469USA

10 Title: METHOD OF CORRECTING A MASK LAYOUT

To: Commissioner for Patents

P.O. BOX 1450

Alexandria, VA 22313-1450

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Subject: Response to the Office action dated 03/19/2004

Dear Sir:

20 INTRODUCTORY COMMENTS

In response to the Office action identified above, the above-identified application is to be amended as indicated in the following section. Consideration of all amendments is politely requested.